

## Supporting Information

### **Bottom-up synthesized crystalline boron quantum dots with nonvolatile memory effect through one-step hydrothermal polymerization of ammonium pentaborane and boric acid**

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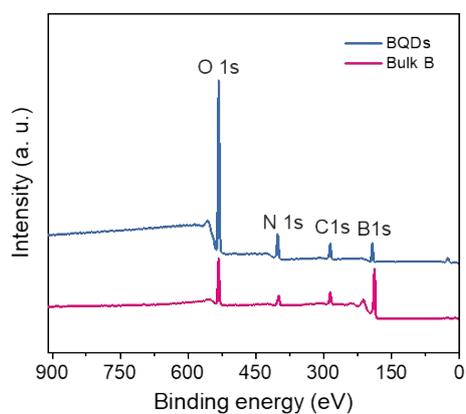
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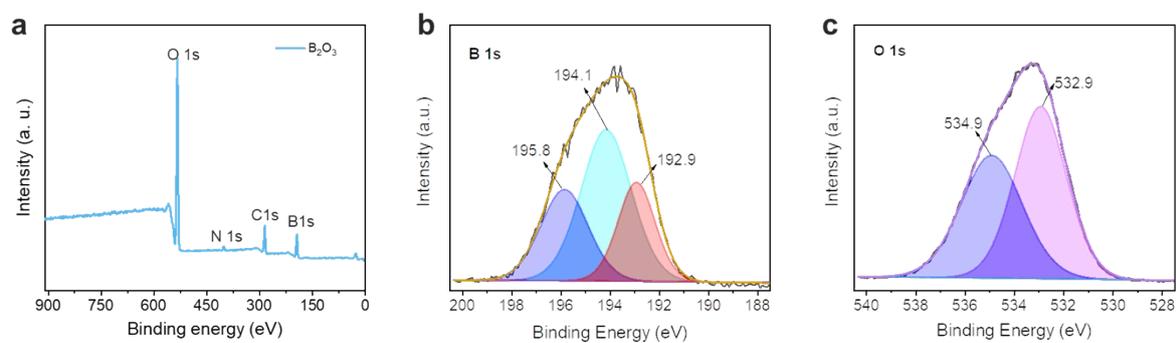
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## Supplementary Figures:



**Fig. S1** XPS survey of BQDs and bulk boron.



**Fig. S2** XPS survey (a), high-resolution B 1s signal (b) and O 1s signal (c) of the commercial B<sub>2</sub>O<sub>3</sub> powder.

## Supplementary Tables:

**Table S1** Components (at. %) of various element species for BQDs and bulk boron.

| No.        | B 1s  | C 1s  | N 1s  | O 1s  | B/O ratio |
|------------|-------|-------|-------|-------|-----------|
| BQDs       | 28.03 | 14.18 | 12.37 | 45.42 | 0.62      |
| Bulk boron | 74.47 | 10.26 | 4.73  | 10.54 | 7.07      |

**Table S2** Ratios of B1s components for BQDs and bulk boron.

| No.        | O–B–O   |        | B–B–O   |        | B–B     |        | B–B–B   |        |
|------------|---------|--------|---------|--------|---------|--------|---------|--------|
|            | BE (eV) | Area/% |
| BQDs       | 192.2   | 8.13   | 190.5   | 8.78   | 188.6   | 15.85  | 187.2   | 67.23  |
| Bulk boron | 192.2   | 3.66   | 190.7   | 4.13   | 188.6   | 19.89  | 187.3   | 72.32  |

**Table S3** Memory device performance of PVP-based composites

| Active layer                  | Switch voltage (V) | ON/OFF ratio | Reference |
|-------------------------------|--------------------|--------------|-----------|
| C60-PVP                       | 2.5                | <10          | [1]       |
| BQDs-PVP                      | 0.5                | $\sim 10^3$  | [2]       |
| MoS <sub>2</sub> -PVP         | 3.3                | $\sim 10^2$  | [3]       |
| N-doped MoS <sub>2</sub> -PVP | 0.7                | $\sim 10^3$  | [4]       |
| BPQD-PVP                      | 2.9                | $\sim 10^4$  | [5]       |
| Au NPs/ZnO nanorod-PVP        | 2.0                | $\sim 10^3$  | [6]       |
| Tri-PVP                       | 10.0               | $\sim 10^2$  | [7]       |
| BQDs-PVP                      | 5.0                | $\sim 10^3$  | This work |

## References

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